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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Masayuki FURUHASHI et al.**

Group Art Unit: **2813**

Serial Number: **10/696,775**

Examiner: **Stephen W. Smoot**

Filed: **October 30, 2003**

Confirmation No.: **7971**

For: **METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE  
INCLUDING THE USE OF A COMPOUND CONTAINING  
SILICON AND NITROGEN TO FORM AN INSULATION FILM  
OF SiN, SiCN OR SiOCN (as amended on September 16, 2005)**

Attorney Docket Number: **032076**

Customer Number: **38834**

**PETITION FOR EXTENSION OF TIME**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

September 16, 2005

Sir:

Applicants petition the Commissioner for Patents to extend the time for response to the Office Action dated May 16, 2005 for one (1) month from August 16, 2005 to September 16, 2005. Attached please find a check in the amount of \$120.00 to cover the cost of the extension. If any additional fees are due in connection with this paper, please charge our Deposit Account No. 50-2866.

Respectfully submitted,

**WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP**

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